

AMENDMENTS TO THE SPECIFICATION

Please amend Paragraph [18] (on page 6) as follows:

a, The substrate 2 consists of a high-purity synthetic quartz glass, which can be obtained under the name "Suprasil" and which has a refraction index of $n = 1.5$ in the wavelength of $\lambda = 248$ observed here. In other embodiments, the substrate can also consist of a crystalline substance, in particular a fluoride like calcium fluoride. The first layer 5, which is directly applied to the surface 3 consists substantially of aluminum oxide (~~Al₂O₃~~) (Al₂O₃), which has a higher refraction index in the active wavelength of approx. $n = 1.69$ compared to the substrate. The high refractive layer 5 adjacent to the substrate has a layer thickness of approx. 64.2 nm or approx. 0.26λ respectively, and is the thickest individual layer of the multilayer system 4. The second layer 6, which is stacked thereupon, consists substantially of magnesium fluoride (~~MgF₂~~) (MgF₂), which compared to the first layer and the substrate 2 has a low refraction index of approx. $n = 1.41$. With a layer thickness of approx. 10 nm, this layer is very thin. The layers 7, 8, 9, 10 stacked thereupon are, in this order, aluminum oxide (13.4 nm) magnesium fluoride (37.2 nm), aluminum oxide (30.5 nm), and magnesium fluoride (52.1 nm).

Please amend Paragraph [24] (on pages 7-8) as follows:

a2 It is explained in Fig. 3 that, if needed, coatings according to the invention may also effect further reduction of reflection in both wavelength ranges indicated. For example, a multilayer system with ten individual layers is described that interchangeably comprises aluminum oxide and magnesium oxidefluoride. The layer system can be characterized with the notation above as follows:

S | 76.5 / A | 11.0 / M | 18.0 / A | 23.4 / M | 15.7 / A | 70.0 / M | 73.0 / A | 47.7 / M |

Q2

37.2 / A | 45.8 / M | (2)

Please amend Paragraph [25] (on page 8) as follows:

Q3 The layer adjacent to the substrate again consists of aluminum oxide in this layer with a total thickness of approx. 418 nm. The thickest individual magnesium ~~oxide~~fluoride layer has a layer thickness of approx. 70.0 nm and is situated approx. in the middle of the layer stack. The ratio of the sum of the low refractive material and high refractive material layer thicknesses is approx. 0.9.
